

<b>Notice of References Cited</b>	Application/Control No. 10/698,865	Applicant(s)/Patent Under Reexamination FORESTER, LYNN	
	Examiner Andrew O. Arena	Art Unit 2811	Page 1 of 1

**U.S. PATENT DOCUMENTS**

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
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	C	US-			
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	K	US-			
	L	US-			
	M	US-			

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**NON-PATENT DOCUMENTS**

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	U	Morisawa, T et al. "Direct Patterning of Spin-on-Glass Materials by ArF Excimer Laser Irradiation and Their New Application to Hard-mask Processes" Jpn. J. Appl. Phys. Vol. 35 (1 Dec 1996) Pt. 1, No. 12B. Pg. 6366-6369. The Whole Document.
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\*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)  
Dates in MM-YYYY format are publication dates. Classifications may be US or foreign.